

Technical Data Sheet

MS-6941900
MS-6941800
01
Sep. 2014

TAIYO INK MFG. CO., LTD.

Office: 900 Hirasawa, Ranzan-machi, Hiki-gun, Saitama, 355-0215 Japan

Marketing office : TEL:+81-493-61-2832 FAX:81-493-61-2833

Technical Development Div. : TEL:+81-493-61-2728 FAX:81-493-61-2729

PSR-4000 LEW7S / CA-40 LEW7S

(UL Suffix : PSR-4000KB/CA-40KB)

1. FEATURES :

PSR-4000 LEW7S / CA-40 LEW7S is liquid photoimageable solder mask (alkaline development type) for screen printing with following features:

- White color, Halogen free
- Sulfur free
- High resolution
- High Reflectance
- Excellent discoloration resistance against UV rays and heat

2. SPECIFICATION :

| | |
|-------------------|--|
| Main agent | PSR-4000 LEW7S |
| Hardener | CA-40 LEW7S |
| Color* | White |
| Mixing ratio | Main agent: 85 / Hardener : 15 (By weight) |
| Viscosity* | 160± 15dPas (Cone plate type Viscometer, 5min ⁻¹ / 25deg.C) |
| Solid Content* | 75±3wt% |
| Specific gravity* | 1.6±0.1 |
| Tack dry window* | 80deg.C / 60min (Maximum) |
| Exposure energy* | 500~700mJ/cm ² (under mylar film) 350~490mJ/cm ² (on solder mask) |
| Pot life* | 24 hours (stored in dark place at less than 25deg.C) |

*After mixing

** After manufacturing

Technical Data Sheet

MS-6941900
MS-6941800
01
PSR-4000 LEW7S / CA-40 LEW7S

3. PROCESS CONDITION

| PROCESS | | RANGE |
|---------------|--|---|
| Substrate | FR-4, 1.6 mm | |
| Pre-treatment | Acid treatment - Buff scrubbing | |
| Printing | 100 mesh-count, Tetron screen | 80~120mesh |
| Hold time | 10 min | 10~20 min |
| Tack free | <ul style="list-style-type: none"> ➤ Both sides simultaneous exposure 1st printing : 80deg.C / 15min. 2nd printing : 80deg.C / 25min. (Hot air convection oven) ➤ Single side exposure 80deg.C/ 30min. (Hot air convection oven) | 80deg.C/10~25min. 80deg.C/20~35min. 80deg.C/30~60min. |
| Exposure | 7kw Mwtal Halide Lamp(ORC-680) 600mJ/cm ² (under art work film) 420mJ/cm ² (on solder mask) | 500~700mJ/cm ² 350~490mJ/cm ² |
| Hold time | 10min. | 10~20min. |
| Development | Aqueous alkaline solution : 1wt% Na ₂ CO ₃ Temperature of developer : 30deg.C Spray pressure : 0.20Mpa Developing time : 60sec. | 0.15~0.25MPa 45~75sec. |
| Water rinse | Temperature : 25deg.C Spray pressure : 0.2MPa Rinsing time : 45sec | Below 30deg.C 0.1~0.15MPa 45~60sec. |
| Post cure | 150deg.C / 60min. (Hot air convection oven) | |

REMARKS:

For applying legend ink, solder mask should be cured for 30 minutes at 150deg.C, and then legend ink is to be cured at 140deg.C.20 minutes 2 cycles.

In case of not applying legend ink, final bake at 150deg.C for 60 minutes.

Technical Data Sheet

MS-6941900
MS-6941800
01
PSR-4000 LEW7S / CA-40 LEW7S

4. ATTENTION ON EACH PROCESS:

Recommendable workshop condition

- Operation under yellow lamps(UV cut) in a clean room with ambient temperature at 20~25deg.C / 50~60%RH.
- Open up the package when it becomes ambient temperature. Stir the hardener well first before mixing with the main agent. Keep stirred well when you put the hardener together with the main agent.
- The adequate thickness after curing is 10 to 20 um .
Coating thickness less than the said may lower solder heat resistance, chemical resistance and Tin plating resistance.
Coating thickness more than the said may cause undercut problem and insufficient tackiness.
- As curing conditions and windows are variable depending on the type of the drying oven, the board quantity to input, etc., set it suitable to your process after testing.
- As exposure energy is variable depending on material type of substrates (UV absorbent, imide-type material etc.) and on coating thickness, prior testing on resolution (no undercut), surface gloss level and shoot-through, etc. should be conducted to set to the optimum condition.
- Control well the quality of developing agent in its density, temperature, spray pressure and dwelling time. Insufficient control may cause deterioration in developability or undercut.
- Final baking condition should be set with consideration of curing time of nomenclature ink. Shortage or excess in curing may cause deterioration of end properties.
- In case of Ni/Au plating, curing time of nomenclature ink should be considered for setting final baking condition of solder mask. Overcure causes lower Ni/Au resistance.

| | |
|-----------------------------|--|
| Technical Data Sheet | MS-6941900 MS-6941800 01 PSR-4000 LEW7S / CA-40 LEW7S |
|-----------------------------|--|

5. CHARACTERISTIC

(1) DEVELOPMENT TOLERANCE WINDOW:

| | | | | |
|---------------------------------|-------|-------|-------|---------|
| Drying time (80deg.C / min.) | 40 | 50 | 60 | 70 |
| Developability | Clean | Clean | Clean | Residue |

(2) PHOTO SENSITIVITY:

| Item | Thickness | Energy | Developing time | Result |
|--|-----------|---|-----------------|---------|
| Sensitivity Kodak No.2 (Step density tablet) | 22+/-2um | 400mJ/cm ² (280mJ/cm ²) | 60sec. | 8 step |
| | | 600mJ/cm ² (420mJ/cm ²) | | 10 step |
| | | 800mJ/cm ² (560mJ/cm ²) | | 11 step |
| Resolution (Between QFP pads) | 40+/-2um | 400mJ/cm ² (280mJ/cm ²) | 60sec. | 80 um |
| | | 600mJ/cm ² (420mJ/cm ²) | | 70 um |
| | | 800mJ/cm ² (560mJ/cm ²) | | 60 um |

The exposure energy is measured on under artwork film (on solder mask) by using ORC HMW-680, 7Kw, metal halide lamp.

| | |
|-----------------------------|--|
| Technical Data Sheet | MS-6941900 MS-6941800 01 PSR-4000 LEW7S / CA-40 LEW7S |
|-----------------------------|--|

(3) PROPERTIES:

| Item | Test method | Test result | | | | | | | | | | | | | | | |
|------------------------|---|---|--|---------|--------------|----------|----|----|--------|----|----|--------|----|----|--------|----|----|
| Adhesion | TAIYO internal Test Method Cross hatch tape peeling | 100 / 100 | | | | | | | | | | | | | | | |
| Pencil hardness | TAIYO internal Test Method No scratch on copper foil surface | 6H | | | | | | | | | | | | | | | |
| Solder heat resistance | Rosin flux, Solder float:260deg.C/ 10sec. (1cycle) | Pass | | | | | | | | | | | | | | | |
| Solvent resistance | Tape-peel test after immersion in PGM-AC, 20deg.C.,20min. | Pass | | | | | | | | | | | | | | | |
| Acid resistance | Tape-peel test after immersion in 10 vol % H ₂ SO ₄ , 20deg.C.,20min. | Pass | | | | | | | | | | | | | | | |
| Alkaline resistance | Tape-peel test after immersion in 10 wt% NaOH, , 20deg.C.,20min. | Pass | | | | | | | | | | | | | | | |
| Electroless gold plate | TAIYO's Internal Test Method Ni 3um Au 0.03um | Pass | | | | | | | | | | | | | | | |
| Insulation resistance | IPC comb type B pattern Humidify : 25-65deg.C,90% RH, DC100V for 7 days Measurement : DC500V / 1 min value at room temperature | Initial 1.0×10 ¹³ Ohm Conditioned 1.0×10 ¹² Ohm | | | | | | | | | | | | | | | |
| Reflectance ratio | TAIYO's Internal Test Method KONICA-MINOLTA(CM-2600d) Pretreatment ; Reflow 285deg.C x 3times Solder mask thickness ; 20um(on Cu) | <table style="margin-left: auto; margin-right: auto;"> <thead> <tr> <th></th> <th>Initial</th> <th>Pretreatment</th> </tr> </thead> <tbody> <tr> <td>Y value:</td> <td>87</td> <td>85</td> </tr> <tr> <td>460nm:</td> <td>88</td> <td>83</td> </tr> <tr> <td>520nm:</td> <td>87</td> <td>85</td> </tr> <tr> <td>640nm:</td> <td>86</td> <td>85</td> </tr> </tbody> </table> | | Initial | Pretreatment | Y value: | 87 | 85 | 460nm: | 88 | 83 | 520nm: | 87 | 85 | 640nm: | 86 | 85 |
| | Initial | Pretreatment | | | | | | | | | | | | | | | |
| Y value: | 87 | 85 | | | | | | | | | | | | | | | |
| 460nm: | 88 | 83 | | | | | | | | | | | | | | | |
| 520nm: | 87 | 85 | | | | | | | | | | | | | | | |
| 640nm: | 86 | 85 | | | | | | | | | | | | | | | |
| Sulfur content | BS EN14582(2007)/Combustion Method Detection Limit ; 50ppm | N.D. (Not Detected) | | | | | | | | | | | | | | | |

Note : The above-mentioned test data is just for reference, not to guarantee the result.

6. Attention

- A. All test data shown above in this technical data sheet are based on our laboratory test result and only for reference, not guarantee the same on your process.
- B. All chemicals used in this product might have unknown toxicity. Please handle with your most care referring to the MSDS for use.
- C. No intentional use of RoHS subjected 6 substances (Lead, Cadmium, Mercury, Hexavalent chromium, PBBs and PBDEs) for this product